Inverse Design Methods for Novel, High-Performance and Manufacturable Components for Photonic Integrated Circuits

Presented by:



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- Over 4,500 members within OSA

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Inverse Design Methods for Novel, High-Performance and Manufacturable Components for Photonic Integrated Circuits





Dr. James Pond is the CTO and co-founder of Lumerical Inc. and is a driving force behind the company's core software algorithms, technology, and advanced photonic modeling capabilities. He has almost two decades of experience in optical and photonic simulation, and is the author of numerous papers, patents and conference presentations.Prof. Benjamin Eggleton is the Director of The University of Sydney Nano Institute. He also currently serves as the co-Director of the NSW Smart Sensing Network (NSSN).

Dr. Jens Niegemann received his PhD in theoretical physics in 2008 from the University of Karlsruhe, Germany. In 2015 he became Principal Scientist at Lumerical Inc. where he focuses on the development and implementation of efficient algorithms for photonic simulations. Dr. Niegemann has contributed to more than 50 peer-reviewed publications and conference presentations.

Please join me to welcome Dr. Pond and Dr. Niegemann.





Question & Answer



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Inverse Design Methods for Novel, High-Performance and Manufacturable Components for Photonic Integrated Circuits





Lumerical Inc. February 20th, 2020





- Motivation and Introduction
- Parametric Shape Optimization
- Topology Optimization
- Summary
- Q&A







Motivation and Introduction



Photonic integrated circuits (PICs) are becoming increasingly more complex



Individual photonic components need to become:

- more efficient
- more tolerant against manufacturing defects or variations
- more compact



Traditional Forward Design



- Traditional design often guided by physical insight
- Might use parameter sweeps or optimization in a small (e.g. 2-5) number of parameters
- Has produced a large library of template devices over the past decades
- But: Time-consuming and often difficult to generalize (e.g. to broad-band devices)



. 2-5) number of parameters bast decades to broad-band devices)



Photonic Inverse Design



- User can target an arbitrary figure of merit (FOM)
- Still allows to use physical insight (or an existing design) to seed the process
- Efficient optimizers allow a much larger number of design parameters
- Here: gradient based algorithms which use the adjoint method to efficiently compute ∇F



The general building blocks of a PID method



- Many combinations have been studied in literature over the past decade or so
- They each have their own advantages and disadvantages



The general building blocks of a PID method



- Many combinations have been studied in literature over the past decade or so
- They each have their own advantages and disadvantages
- Here, we focus on a specific combination
- For more details on PID, see review articles (and references therein):
 - "Topology optimization for nano-photonics", Jensen, J. and Sigmund, O. Laser & Photon. Rev. 5, 308-321. (2011)
 - "Inverse design in nanophotonics", Molesky, S. et al., Nat. Photon. 12, 659–670 (2018)



Parametrization: Shape/Topology





- Output And A States and A St parametrization
- Requires good initial design \bigcirc
- Parametrization may still be too restrictive (:)



- \odot
- enforce
- $(\cdot \cdot)$ generalize



User only specifies footprint and materials Often yields very high-performance Generation Constraints Manufacturing constraints more difficult to

Design often unintuitive and not easy to



EM-Solver: FDTD

- Robust, well-established method based on the Yee grid
- Very fast, especially for low/medium accuracy requirements
- Broadband optimization is easy and cheap
- Scales well to large 3d systems
- For Topology Optimization: rectilinear grid matches parametrization







Optimizer: Gradient Based

- Running simulations to evaluate figure-of-merit *F* is generally expensive.
- Gradient methods find local solutions very quickly.
- They require an estimate of the gradient:

$$\nabla_p F = \left(\frac{\partial F}{\partial p_1}, \cdots, \frac{\partial F}{\partial p_N}\right)$$

• The gradient determines the direction of steepest descent:







Gradient Calculation: Adjoint sensitivity analysis, a long history

A long history over many decades in many fields including atmospheric science, fluid dynamics, electromagnetics, structural mechanics and more

Some examples of early work:

- Hall, M. C. G., D. G. Cacuci, and M. E. Schlesinger, 1982: Sensitivity analysis of a radiative convective model by the adjoint method. J. Atmos. Sci., 39, 2083-2050
- J. W. Bandler, Qi-Jun Zhang and R. M. Biernacki, "A unified theory for frequency-domain simulation and sensitivity analysis of linear and nonlinear circuits," in IEEE Transactions on Microwave Theory and Techniques, vol. 36, no. 12, rol 1661-0659, Dec. 1988.
- O. Sigmund "A 99 line topology optimization code written in MATLAE", Structural and Multidisciplinary Optimization 21(2), 2001, pp. 120-127 • tacom
- ...

Early use with FDTD simulation

- review! N. K. Nikolova, H. W. Tum and M. H. Bakr, "Sensitivity analysis with the FOTD method on structured grids," in IEEE Transactions on Microwave Theory and Techniques, vol. 52 no. 4, pp. 1207-1216, April 2004.
- M. A. Swillam, M. H. Bakr, and X. Li, "Accurate sencitivity analysis of photonic devices exploiting the finite-difference time-domain central adjoint • variable method," J. Applied Optics, vol. 46, no. 9, pp. 1492 1499, March 2007
- . . .

Use in integrated photonics

- J. Jensen and O. Sigmund, "Topology optimization for nano-photonics," Laser & Photon. Rev., 5: 308-321 (2011)
- Alexander Y. Piggott, Jesse Lu, Konstantinos G. Lagoudakis, Jan Petykiewicz, Thomas M. Babinec & Jelena Vučković, "Inverse design and • demonstration of a compact and broadband on-chip wavelength demultiplexer", Nature Photonics volume 9, pages 374–377 (2015).
- Christopher M. Lalau-Keraly, Samarth Bhargava, Owen D. Miller, and Eli Yablonovitch, "Adjoint shape optimization applied to electromagnetic design," Opt. Express 21, 21693-21701 (2013).

...



Gradient Calculation: The Adjoint Method

- Adjoint method allows for **efficient** evaluation of F and its gradient
- Only two simulations (independent of the number of parameters) are required:





Gradient Calculation: The Adjoint Method for FDTD

- Here, we use an approach based on Green's functions/the Born approximation
- Requires no change to the solver
- Our implementation started as a collaboration with Christopher Keraly from Eli Yablonovitch's group (UCB)
- (Almost) Everything we present here today is freely available in an open-source project called "lumopt"
- Hosted on github under a MIT license at <u>https://github.com/chriskeraly/lumopt</u>



Christophe	•
Christopher	

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Python based continuous adjoint optimization wrapper for Lumerical								
· 44	commits	🖗 1 branch	O packages	🟷 0 releases	🞎 4 contribu	utors	♣ View license	
Branch: rele	ase - New pul	l request				Find file	Clone or download -	
R areid-v	Reid-van Added topology optimization and enhancements					c350a1a on Jul 3, 2019		
D QA	QA Added topology optimization and enhancements 7 months ago				7 months ago			

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Adjoint shape optimization applied to electromagnetic design

M. Lalau-Keraly,^{1,*} Samarth Bhargava,¹ Owen D. Miller,² and Eli Yablonovitch¹

s, Vol 21, Issue 18, 2013





Parametric Shape Optimization

Y-splitter example: Designing a smaller splitter

Prior art

- Inverse design using particle swarm 1. optimization
- Output waveguides added post 2. optimization

- Example splitter • Parametric shape includes output waveguides
- 20 parameters
- Smaller footprint



https://github.com/lukasc-ubc/SiEPIC_EBeam_PDK

A compact and low loss Y-junction for submicron silicon waveguide Yi Zhang, et al, Optics Express Vol. 21, Issue 1, pp. 1310-1316 (2013)







Y-splitter example: Run fast 2D optimization

This example takes < 60 minutes to run:



FINAL FOM = [0.49560308] FINAL PARAMETERS = [0.2 0.26701897 0.48560055 0.67317026 0.69742398 0.727 36151 0.69563423 0.74014193 0.69735868 0.7383804 0.82057129 0.99880643 1.21080748 1.40641413 1.58424313 1.72710327 1.84192843 1.90636349 1.96069338 1.99607748] >>>





Co-Optimization



Co-optimization:

- Run multiple optimizations concurrently
- Optimizations share same parameters
- Figure of merit or structure can be different

Example uses:

- Dual polarization devices (different FOM)
- Unequal splitting ratio (different FOM)
- De-multiplexing (different FOM)
- Optimize process corners (different geometry)



Co-optimization: Robust splitter

- Build a splitter tolerant to manufacturing error •
- Co-optimize 2 different shapes (same parameters)
- "Over etch" slightly smaller than nominal
- "Under etch" slightly larger than nominal
- Same FOM function •





Co-optimization: Robust splitter

Co-optimization of +/- 14nm on edge position



- Problem setup similar to before
- Setup 2 optimizations
- Sum the figures of merit
- 2 FDTD simulations/FOM/iteration



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Nominal device

FOM = 2 = ideal



Measured Results of Devices Designed with Lumopt



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Designed and fabricated during the

"SiEPIC-Passives workshop with Applied Nanotools fabrication",

Organized by Lukas Chrostowski at UBC (siepic.ubc.ca)



Example: Grating Couplers

- Grating Couplers (GCs) are important devices for PIC
 - Don't require additional process steps
 - In/out-coupling anywhere on the chip
 - Allow for automatic wafer-scale testing
 - Alignment easier than alternative coupling techniques
- But they have challenges as well:
 - Not trivial to get high coupling efficiencies
 - Not intrinsically broad-band
 - Constrained by manufacturing capabilities •
 - Large design space (50+ parameters) makes optimization challenging





Systematic Optimization of Grating Couplers

A single-etch GC in 2d has \approx 50 parameters



- We assume fiber angle (10 deg), Si layer thickness (220nm), BOX thickness (2um) as fixed
- Outcome of optimization strongly depends on initial guess
- Systematic Approach to design highly efficient GCs
 - Physical knowledge or analytic solutions provide a good initial guess
 - Use sequence of optimizations which gradually increase complexity



Optimization of basic partial-etch GC

1. Use physical insight [1] to design linearly apodized coupler (only 4 parameters)



[1] R. Marchetti et al., "High-efficiency grating-couplers: demonstration of a new design strategy", Scientific Reports 7, 16670 (2017), <u>https://www.nature.com/articles/s41598-017-16505-z</u>



Optimization of basic partial-etch GC

2. Use previous result as initial guess for a full optimization (each wall position is free to move)





Introducing manufacturing constraints





Broadband Grating Coupler

- Starting with a grating optimized for C-band (40nm bandwidth)
- Re-optimize targeting 100nm and 120nm



https://kx.lumerical.com/t/broadband-grating-coupler-design-bandwidth-vs-peak-efficiency/40954







Topology Optimization

Topology Optimization

- Providing a parametrization can be difficult or overly restrictive
- With topology optimization, the user only provides **footprint**, **material parameters** and **FOM**



- Solver automatically discretizes the domain and tries to find best solution
- Challenge is to ensure that the resulting structure can be manufactured

FOM: Transmission into upper arm



Parametrization

• Use a rectilinear grid for the design area.



- Each cell is an optimization parameter $\rho_i \in [0,1]$ (typically N > 10000)
- Parameter maps directly to permittivity: $\epsilon_i = \epsilon_{low} + \rho_i(\epsilon_{high} \epsilon_{low})$ •





General procedure

Our topology optimization method uses a two-phase approach:



Jensen, J. and Sigmund, O., "Topology optimization for nano-photonics", Laser & Photon. Rev. 5, 308-321 (2011)



Greyscale Phase: Ensure Manufacturability

• Employ smoothing with a **user-specified radius** *R*

$$\bar{\rho}_j = \frac{1}{N} \sum_j \rho_j w (x_i - x_j)$$

- Typical values: R = 50 200 nm
- Leads to smooth designs that are "lithography-friendly"
- Also a first step in reducing small features
- Instead of simple filter, we can also use transfer function of a specific lithography system







Mapping to Permittivities: Heaviside Filter

• Employ Heaviside filter:

$$\tilde{\rho} = \frac{\tanh(\beta\eta) + \tanh(\beta(\bar{\rho}_i - \eta))}{\tanh(\beta\eta) + \tanh(\beta(1 - \eta))}$$

- Continuously increases β from 1 to around 1000
- Terminates once the design is sufficiently binary



Simple Example – Y-Splitter





Robust Design

- As with parametric shape optimization, we can co-optimize 3 different shapes:
 - "Nominal"
 - "Over etch" slightly smaller than nominal
 - "Under etch" slightly larger than nominal



Under etch





Binarization Phase: Heaviside Filter

 ϵ_{high}

Ψ

 $\epsilon_{\sf low}$ 0

• Heaviside filter:

$$\tilde{\rho}_{i} = \frac{\tanh(\beta \eta) + \tanh(\beta(\bar{\rho}_{i} - \eta))}{\tanh(\beta \eta) + \tanh(\beta(1 - \eta))}$$

- Parameter η shifts the binarization threshold
- In combination with the smoothing, this effectively moves the boundaries



Robustness to Manufacturing Tolerances (±20nm)





Enforcing Minimum Feature Size Constraints

- Even with filtering, topology optimization often yields structures that contain small features which are challenging to manufacture.
- To make structures manufacturable, we need to explicitly enforce constraints
- Here, we implement an algorithm originally proposed for structural mechanics in

Zhou, M. et al. "Minimum length scale in topology optimization by geometric constraints", Comput. Methods in Appl. Mech. Eng 293, 266-282 (2015)

- It does not require additional simulations and is cheap to calculate
- Adds a simple constraint/penalty term to the optimization



Example: 4-Channel Wavelength Demultiplexer in the O-band

Use topology optimization to design a 4-channel CWDM demultiplexer



Best known theoretical proposals have a footprint of over 1 mm^2 , here we aim for $36 \mu \text{m}^2$, a reduction of around 5×10^4 !



4-Channel Wavelength Demultiplexer in the O-band





With constraints (150nm min feature size)





Field distribution

• Plotting the real part of H_z component



 $\lambda = 1270$ nm

 $\lambda = 1290$ nm

- Scale of colorbar is identical in all plots
- No extreme hotspots

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 $\lambda = 1310$ nm

$\lambda = 1330$ nm





- Photonic Inverse Design has transitioned from a research topic to a design method
- Parametric shape optimization can quickly improve existing designs
- Topology optimization can yield large improvements in both performance and footprint
- Strict enforcement of minimum feature sizes is possible and necessary to generate manufacturable designs





Q&A